



# Efficiency and mechanism of dislocation density reduction during heteroepitaxial growth of diamond for detector applications

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- Growth and nucleation of heteroepitaxial diamond layers on Ir(001)
- Defects in crystals
- Dislocation density reduction by increasing thickness
- Raman and PL measurements on diamond cross sections
- Epitaxial lateral overgrowth (ELO)



## Bias enhanced nucleation (BEN)

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 bombardment of substrate surface with positively charged ions from a hydrogen / methane plasma

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- electric field ~ several kV/cm
- $\rightarrow$  nucleation density reaches

<u>10<sup>11</sup> cm<sup>-2</sup></u>



### Multi-layer-system Ir/YSZ/Si(001)

- Si: + high quality crystals
  - + large size
  - + low price



 $\rightarrow$  Low thermal stress!

**but**: diamond directly on silicon never reached single crystal quality

<u>Multi-layer-system (Ir/YSZ/Si(001))</u> YSZ: yttria ( $Y_2O_3$ ) - stabilized zirconia (ZrO<sub>2</sub>)

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Lattice misfit related to diamond ~34,3% for Si and ~7,6% for Ir

Diamond on Ir:

- + extremely high density of oriented nuclei
- + low mosaic spread of grains



#### GROWTH OF SINGLE CRYSTAL IRIDIUM ON SILICON VIA OXIDE BUFFER LAYERS





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## Growth by "Microwave enhanced plasma chemical vapour deposition" (MWPCVD)

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Schematic view and photograph of a CVD reactor.





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## Defects in crystals



#### Point defects (0D)

Vacancies, interstitials, antisites, ...





Neu et al., New J. Phys. 13 (2011) 025012

http://en.wikipedia.org/wiki/Crystallographic\_defect

#### Line defects (1D)

#### Edge/screw dislocations, mixed types



Hull & Bacon, Introduction to dislocations, 1984, Pergamon

#### Planar defects (2D)

Stacking faults, grain boundaries, ...



http://amadm.unileoben.ac. at/ReyesHuamantinco\_And rei\_B\_2.jpg



C. Kittel: Einführung in die Festkörperphysik, 14th ed. (2006)

#### Bulk defects (3D)

Voids, precipitates, ...



http://www.tf.unikiel.de/matwis/amat/mw\_for\_et/kap\_4 /illustr/korngrenze1.gif

Symmetric small angle tilt boundary in cubic lattice (1 degree of freedom, in general: 5)







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### Change during growth process





0.6 µm



8 µm



M. Schreck et. al. Journal of Applied Physics **91**, 2002

34 µm

Plan-view TEM images of epitaxial diamond layers grown on  $Ir/SrTiO_3(001)$  with increasing thickness.



 $\rightarrow$  no longer isolated mosaic blocks bounded by polygonized network of grain boundaries

Highly oriented mosaic crystal becomes defective single crystal!

Drawing of the defect lines for 34  $\mu$ m.



<30nmT

### Variation of the defect structure with film thickness





#### Phase 3: transition to single crystal layer

single crystal region with isolated and clustered dislocations mosaic block region

highly oriented diamond

layer: individual mosaic

blocks separated by small

#### Phase 2:



 $\rightarrow$  possible only if approach distance between two TDs with different Burgers vectors reaches a critical value r<sub>a</sub>.

During growth, dislocations

Changing distance can happen by means of glide, climb or cross slip of dislocations. No real movement of dislocations but "effective" climb, glide ... during growth



#### Phase 1:

isolated diamond crystallites on iridium layer





## Variation of etch-pit density with crystal thickness







## Variation of the Raman and luminescence signal with crystal thickness



RAMAN PEAK WIDTH (cm<sup>-1</sup>) (mrl) NOILISOd - 200-11.5 7.5 5.5 9.5 3.5 1.5 200 LATERAL 150 (a) 100 Ó 200 400 600 800 1000 RAMAN PEAK WIDTH (cm<sup>-1</sup>) 11 2.4 10-9. 2.2 8 7 2.0 6 480 520 560 5 3. 2 200 400 600 800 1000 0 LUMIN. BACKGROUND (a.u.) 0.8 0.6 0.0 200 400 600 800 1000 CRYSTAL THICKNESS d (µm)

Nitrogen is switched off at d=500 µm

growth side

Drop in Raman FWHM, when nitrogen flux is switched off

→ Broadening caused by point defects generated by adding nitrogen?

But also: Decrease of Raman FWHM with increasing thickness of the sample!

Possibility of creating a "calibration curve" of Gaussian broadening vs. etch-pit density with previous data?

C. Stehl et al. APL **103**, 151905 (2013)



### Correlation of Gaussian broadening and etch-pit density









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## Raman- and PL-measurements on diamond cross sections





SEM-image of the cross section of a (001)-diamond layer

 $\rightarrow$  bright and dark stripes are risers/terraces

 $\rightarrow$  PL-/Raman-mapping of the orange marked section

Measurements performed by C. Stehl



## Raman- and PL-measurements on diamond cross sections



#### normalized SiV-intensity





Raman-FWHM (cm<sup>-1</sup>)



 $\rightarrow$  Enhanced SiVintensity in dark stripes  $\rightarrow$  Enhanced NV<sup>0</sup>intensity in dark stripes  $\rightarrow$  defect bands approximately in growth direction (tilt of ~12°)

- Identification of dark/bright stripes as risers/terraces?
- Correlation of Raman-FWHM broadening with etch-pit/dislocation density
  → Application of formerly obtained correlation data



Measurements performed by C. Stehl



## **Dislocation network**



Correlation of gaussian broadening with etch-pit density (using formerly obtained curve for calibration):



The estimated deduced equivalent etch-pit density varies by an order of magnitude over the measured cross section!

→ Variation caused by dislocation networks which develop out of grain boundaries with extended growth.



### **Dislocation network**



## Image of growth surface:

Clustering of dislocations in bands











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Further extended growth not practical  $\rightarrow$  change of strategy needed!







## Thank you for your attention!

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